

AZ1500(20CP)&(4.4CP)化学试剂半导体光刻胶

产品名称	AZ1500(20CP)&(4.4CP)化学试剂半导体光刻胶
公司名称	厦门良厦贸易有限公司
价格	.00/件
规格参数	
公司地址	中国（福建）自由贸易试验区厦门片区中埔社10190号（注册地址）
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产品详情

抛光耗材方面：fujimi抛光液103，compol-80，光纤抛光液，金属抛光液，氧化铈抛光皮；5，电子化学品方面：ITO蚀刻液，BOE蚀刻液，铬蚀刻液，去胶液，显影液，晶片切割保护液；

6，供用美国安智光刻胶:AZ1500，AZ6130,等各型号光刻胶；

AZ 1500 HS family was developed in 1990. The background for this development was the fact that in making discrete and bipolar semiconductor devices wet-etching is still very common. For wet-etching adhesion is the most important issue. Especially on aluminium the mousebite-phenomenon is well known. To solve this problem we have chosen a low molecular weight novolak resin fraction resulting in significantly improved adhesion and also very high photospeed (therefore the suffix High Speed). Meanwhile AZ 1500 HS has proven its superior performance in several production lines and lead to less rework and higher yields.

All AZ 1500-series resists are compatible with all common developers used for positive photoresists, like AZ 351B (diluted 1:4), 0.5% NaOH solution and metal ion free developers like AZ 726MIF. While AZ 1500-family and AZ 1514H are optimised for best process latitude at 50 - 60 seconds development time, AZ 1500HS-family performs best at 20 - 30 seconds development time resulting in a high throughput lithographic process.